

IN THE CLAIMS:

Please amend claims 11-13, 15-18 and 20 as shown on the complete list of claims that is presented below.

Claims 1-10 (canceled).

Claim 11 (currently amended). A production process for a semiconductor chip, comprising the steps of:

providing [[an]] a first internal interconnection and a second internal interconnection on a semiconductor substrate;

forming a surface protective film over the internal interconnections;

forming [[an]] a first opening and a second opening in the surface protective film to respectively expose a portion of the first internal interconnection and a portion of the second internal interconnection;

forming a bump projecting from the surface protective film on the portion of the first internal interconnection exposed through the first opening; and

forming, after the formation of the bump or simultaneously with the formation of a part of the bump, a surface interconnection electrically connected to the bump and also electrically connected to the second internal interconnection through the second opening, the surface interconnection having a smaller height than the bump, ~~in a predetermined region on the surface protective film except a portion thereof formed with the opening~~.

Claim 12 (currently amended). A process as set forth in claim 11, wherein the bump forming step includes the step of selectively depositing a conductive material on the portion of the first internal interconnection exposed through the first opening,

wherein the surface interconnection forming step includes the step of selectively depositing a conductive material in [[the]] a predetermined region on the surface protective film ~~except the portion thereof formed with the opening.~~

Claim 13 (currently amended). A process as set forth in claim 11,
wherein the conductive material is selectively deposited on the portion of the first internal interconnection exposed through the first opening and in [[the]] a predetermined region on the surface protective film, ~~except the portion thereof formed with the opening,~~ thereby to form a part of the bump and the surface interconnection,

wherein the conductive material is further selectively deposited on the part of the bump to complete the bump which projects from the surface protective film.

Claim 14 (original). A process as set forth in claim 11, further comprising the step of forming a recess in a region of the surface protective film on which the surface interconnection is to be formed before the formation of the bump and the surface interconnection, wherein the surface interconnection is formed in the recess.

Claim 15 (currently amended). A process as set forth in claim 14,
wherein the conductive material is selectively deposited in the first opening and the recess to form [[a]] the part of the bump and the surface interconnection,
wherein the conductive material is further selectively deposited on the part of the bump to complete the bump which projects from the surface protective film.

Claim 16 (currently amended). A process as set forth in claim 15, wherein the selective deposition of the conductive material in the first opening and the recess includes the steps of:

forming a conductive material film over the surface protective film ~~formed with~~ having the first opening and the recess; and

removing the conductive material film except portions thereof ~~formed~~ in the first opening and the recess.

Claim 17 (currently amended). A process as set forth in claim 16, wherein the removal of the conductive material film includes the step of partly polishing away the conductive material film except the portions thereof ~~formed~~ in the first opening and the recess for planarization thereof.

Claim 18 (currently amended): A process as set forth in claim 16, wherein the removal of the conductive material film includes the step of entirely polishing away the conductive material film except the portions thereof ~~formed~~ in the first opening and the recess for planarization thereof.

Claim 19 (original): A process as set forth in claim 14, wherein the recess has a bottom surface located at a lower level than a top surface of the internal interconnection.

Claim 20 (currently amended): A process as set forth in claim 14, further comprising the step of planarizing a surface of the surface protective film ~~between the step of~~ after forming the surface protective film and ~~the step of~~ before forming the first opening and the recess.

Claim 21 (original): A process as set forth in claim 11, wherein the bump includes a peripheral bump to be provided outside a device formation region of a semiconductor substrate which is a base body of the semiconductor chip.

Claim 22 (original): A process as set forth in claim 21, wherein the peripheral bump is configured as surrounding the device formation region.

Claim 23 (original): A process as set forth in claim 21, wherein the peripheral bump is formed in a scribe line region.

Claim 24 (original): A process as set forth in claim 21, wherein the surface interconnection is formed to be connected to the peripheral bump.